

#### The Filmetrics Advantage

- World's leader in tabletop thin-film measurement
- 24-hour phone, e-mail, and online support
  Intuitive analysis software standard with every system

#### **Additional Features**

- Built-in online diagnostics
- Standalone software included
- Sophisticated history function for saving, reproducing, and plotting results

### Automated Thin-Film Thickness Mapping System

Thin-film thickness of samples up to 450 mm in diameter are mapped quickly and easily with the F50 advanced spectral reflectance system. The motorized r-theta stage moves automatically to selected measurement points and provides thickness measurements as fast as two points per second. The F50 has the same precision high-lifetime stage that performs millions of measurements in our production systems.

Choose one of dozens of predefined polar, rectangular, or linear map patterns, or create your own with no limit on the number of measurement points. The entire desktop system is set up in minutes and can be used by anyone with basic computer skills.

#### **Example Layers**

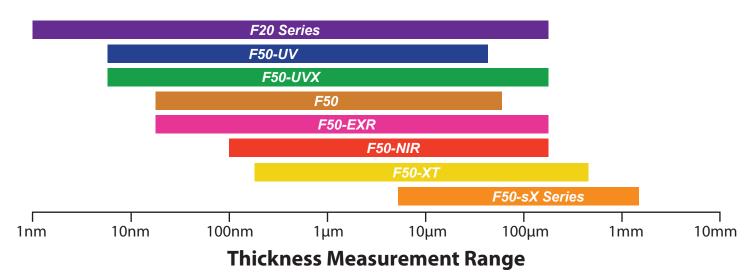
Virtually any smooth, non-metallic film may be measured. Examples include:

SiO <sub>2</sub>	SiN <sub>x</sub>	DLC	Polysilicon
Photoresist	Polymer Layers	Polyimide	Amorphous Silicon

### **Example Applications**

Semiconductor Fabrication	LCD			
Photoresist	Cell Gaps			
Oxides/Nitrides/SOI	Polyimide			
Wafer Backgrinding	<u>ITO</u>			
MEMS	Optical Coatings			
Photoresist	Hardness Coatings			
Silicon Membranes	Anti-Reflection Coating			





Measurement Sp	pecifications	F50-UV	F50-UVX	F50	F50-EXR	F50-NIR	F50-XT		F50-s1310	
Thickness Measurement Range*:		5 nm - 40 µm	5 nm - 250 μm	20 nm - 70 µm	20 nm - 250 µm	100 nm - 250 μm	0.2 μm - 450 μm		7 µm - 2 mm	
Min. Thickness to Measure n and k*:		50 nm	50 nm	100 nm	100 nm	500 nm	2 µm		100 µm	
Wavelength Range:		190 - 1100 nm	190 - 1700 nm	380 - 1050 nm	380 - 1700 nm	950 - 1700 nm	1440 - 1690 nm		1280 - 1340 nm	
Accuracy*: The greater of		0.2% or 1 nm	0.2% or 1 nm	0.2% or 2 nm	0.2% or 2 nm	0.4% or 3 nm	0.4% or 4 nm		0.4% or 50 nm	
Precision:			0.02	1 m 1		0.1 nm <sup>1</sup>	1 nm <sup>1</sup>		5 nm <sup>2</sup>	
Stability:			0.05	וm <sup>3</sup>		0.12 nm <sup>3</sup>	1 nm <sup>3</sup>		5 nm ⁴	
Spot Size:	:	nm, optional d	optional down to 150 μm		600 µm		10 µm			
Light Source Lamp MTBF:			0 Hours 200 Hours	Halogen: 1200 Hours					SLED: >10 years	
General Specifications					200 mm Chuck			300 mm Chuck		
Power Requiremen	ts: 100 - 240	100 - 240 VAC, 50 - 60 Hz, 1		Sample S	Sample Size:		≤ 200 mm diameter		≤ 300 mm diameter	
Dimensions:		14W x 19D x 11H (in) 35.5W x 48.3D x 28H (cm)		Speed (Typical with Vacuum Chuck):		5 points - 5 sec. 25 points - 14 sec.		5 points - 8 sec. 25 points - 21 sec.		
Weight:		35 lbs. (16 kg)			ondony.	56 points - 29 sec.		56 points - 43 sec.		
Computer Requirements				<ul> <li>* Material dependent</li> <li><sup>1</sup> 1σ of 100 measurements of 500 nm SiO<sub>2</sub>-on-Si. Average of 1σ over 20 successive days.</li> <li><sup>2</sup> 1σ of 100 measurements of 100 μm SiO<sub>2</sub>-on-Si. Average of 1σ over 20</li> </ul>						
Interface: USB 2.0										
Operating System										
PC⁵:	Windows XP (SP2) - Latest Windows (64-bit)				successive days. <sup>3</sup> 2σ of daily average of 100 measurements of 500 nm SiO2-on-Si over 20					
Mac:	OS X Lion/Mou	untain Lion run		successive days. <sup>4</sup> 2α of daily average of 100 measurements of 100 µm SiO -on-Si over 20						

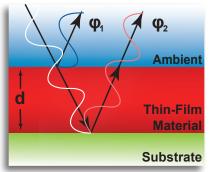
 $^4$  2 $\sigma$  of daily average of 100 measurements of 100  $\mu m$  SiO\_2-on-Si over 20 successive days.

<sup>5</sup> Windows Vista – Latest Windows(64-bit) and a DirectX 10 graphics card required to render 3D wafer maps

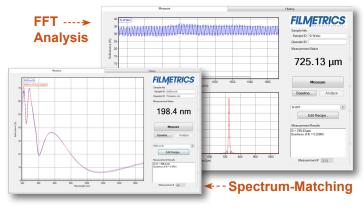


## How Does It Work?

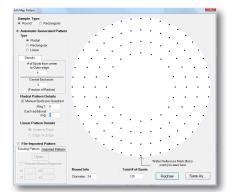
When light encounters an interface between two materials, it is partially reflected. The wave-like nature of light causes reflections from multiple interfaces  $(\phi_1, \phi_2)$  to interfere with each other, resulting in oscillations in the wavelength spectrum



of the reflected light (see image above). From the frequency of these oscillations, we determine the distance between the different interfaces and thus, the thickness d of the materials (with more oscillations meaning greater thickness). Other material characteristics are also measured, such as refractive index and roughness. For the analysis of the spectra, our FILMeasure/ FILMapper software uses two analysis modes: Spectrum-Matching and FFT. In Spectrum-Matching mode, you can analyze thickness, as well as refractive index, whereas FFT mode is only for thickness but is often more robust for thicker films.



## **FILMapper Software – Measurement Automation**



### The Map Pattern Generator

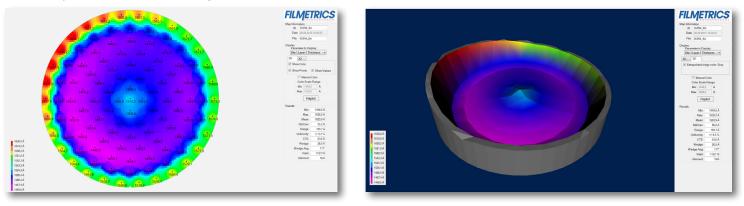
The built-in map pattern generator lets you easily generate the spot patterns needed to measure the relevant area of your samples, thus saving time during data acquisition.

Here are only some of the parameters you can adjust to customize your map's properties:

- · Round or square maps
- · Radial or rectangular patterns
- Center or edge exclusion
- Spot density

### **Measurement Results Visualization in 2D and 3D**

Whether you are measuring reflectance, film thickness, or refractive index, FILMapper lets you display the resulting measurement maps in either 2D or 3D. Switch easily between the maps for the individual measurement parameters and freely rotate 3D profiles to get an optimal view of the results.

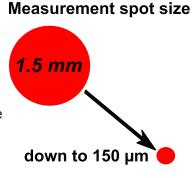




# **Optional Accessories**

### **Overcoming High Surface Roughness**

For samples with a high roughness, spot sizes of 300 µm or 150 µm are available. If an even smaller spot size is needed (e.g. to measure on lateral structures), take a closer look at the <u>Filmetrics F54</u>.



#### Available Chuck Sizes



Select one of our standard chuck sizes of 100 mm, 200 mm, 300 mm, or 450 mm in diameter or ask for a custom-made chuck.

### **Staying Focused**



You'll benefit from our optional autofocus if you're measuring absolute reflectance with high accuracy or if your samples have a significant height variance. It is also important to maintain the small spot size of the sX versions.

### **Bigger Samples and Transmittance**

With the F50-XY, measure samples as big as 590 mm x 550 mm and up. It also allows for measurement of sample transmittance.



# Looking to Do More?

#### Extend your capabilities even further with these related products:



F3 Series for layers as thin as 1 nm thick



<u>F10-RT for simultaneous</u> reflectance and transmittance



F54 Series for micro-spot measurements

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